Low-Frequency Noise in SiGeC-Based pMOSFETs

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Outline

- Performance of SiGeC MOSFETs
 - Comparison Si : SiGe : SiGeC
- Experimental results
 - *** DC and LFN experiments**
 - Trends, variations, modeling
- Discussion on LFN behavior
 - Noise scaling
 - ***** ∆N model, trap density
- Conclusions

Comparison Si : SiGe : SiGeC SiGe SiGeC <u>Si</u> Mobility μ_n/3 ∼µ_{SiGe} ۶µn Relaxed No Strain High **Gate Insulator** Gate Insulator Gate Insulator E_c E_c E_c Gap E_F Ē Tuning Ev Ev Ev $\mathbf{ \cdot }$ Ge

Low-Freq. Noise in pMOSFETs

<u>Si</u> <u>SiGe</u> <u>SiGeC</u>

• **ΔN**

• Δμ

Yes

?

 $S_{I_{D}} = S_{V_{G}} g_{m}^{2}$

G. Ghibaudo, *et al*, SSE, **46**, 393 (2002) Y.-J. Song, *et al*, TED, **50**(4). 1152 (2003) A. Lambert, *et al*, TED, **46**(7), 1484 (1999)

Sometimes

S. Okhonin, et al, TED, **46**(7), 1514 (1999) N. Lukyanchikova, *et al*, EDMO, 181 (2001) G. Ghibaudo, *et al*, SSE, **46**, 393 (2002)

• S_{ID} ~1/_{Area}

Yes

Yes

A. Lambert, et al, TED, 46(7), 1484 (1999)

?

SiGeC pMOSFET Samples



• Alloy

- ♣ SiGe_{40%}C_{1.5%}
- ♣ SiGe_{40%}C_{1%}
- **♦ SiGe**_{40%}C_{0.5%}
- ♣ SiGe_{40%}
- * Si
- Channel Sizes
 - *** Width (W)= 5** μm
 - *** Length (L)=0.1-2**μm
- Number of Samples
 - DC: more than 200
 - LFN: more than 20
- Data Files ~ 3000

DC Experiments



- Wafer Mapping
 - Leakages
 - Proper I-V
- Transfer I-V Curves
 - **₩** V_{GS}= |V_T-0.3V| ... -2V
 - **₩** V_{DS}= -1V ... -50mV
 - **₩** V_{BS}= -0.6 ... +0.6V
- DC Modeling
 - Strong to Weak Inversion
 - Parameter Extraction
- Statistics
 - ***** V_T(V_{BS}), g_m(bias)
 ***** K=I_D/|V_{GS}-V_T|²

1/f and Lorentzian LF Noise



- Biasing
 - **₩** V_{GS}= |V_T-0.1V| ... -2V
 - **₩** V_{DS}= -1V ... -50mV
 - **₩** V_{BS}= -0.6 ... +0.6V
- S_{ID} Spectra (about 800)
 2Hz 1.6kHz
 - ***** S_{I_D}/I_D^2 , S_{I_D}/g_m^2
- Corresponding DC

 - **∦** |_D

g_m

Extensive DC and LFN Data



Numerical data available through www.RDIE.ca Marinov, *et al*, www.RDIE.ca, **1**(1), 1 (2004)

Trend of Noise Results

(SiGe_{40%}C_{1.5%}) PMOS (W=5µm, L=1µm)



Despite variations

• $\mathbf{S}_{|_{\mathbf{D}}} \propto |_{\mathbf{D}}^2$



Distribution - K_F = S_{I_D} \times f / I_D^2

(SiGe_{40%}C_{1.5%}) PMOS (W=5µm, L=1µm)



Log-Normal LFN Model

Exponential-Logarithmic form for noise equation

Exponential



- Noise averaging • K_{F,dB})_{avg} = $\frac{10dB}{N} \sum_{j=1}^{N} \log_{10} \left(\frac{S_{l_D}}{l_D^2} f \right)_j$ • Geometric (arithmetic in dB) • Model parameters • Noise averaging $(\kappa_{F,dB})_{avg} = \frac{10dB}{N} \sum_{j=1}^{N} \log_{10} \left(\frac{S_{l_D}}{l_D^2} f \right)_j - (\kappa_{F,dB})_{avg} \right]^2$
 - Average Noise: K_F=10^{(KF,dB)/10dB}
 - Log-Normal deviation: σ_{dB}
 - # t=(1,...,3) for confidence probability (60%,...,99%)

Population Requirements

- N>250 for K_F and σ_K evaluation
 - Frequency points ≥ 30
 - Bias points ≥ 8
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N>2000 for inspection of distribution

- Frequency points ≥ 50
- Bias points ≥ 60
 Bias points ≥ 60
- Small Population:



Similarity to PE-BJT

M. Sanden, et al, TED, 49(3), 514 (2002)



∆N noise?

∆N model for LFN



G. Ghibaudo, et al, SSE, 46, 393 (2002)

Number fluctuation in all samples for $|V_{GS}-V_T| < 0.2V$

Conclusion

Experiments of SiGeC pMOSFETs

- Detailed LFN measurements
- ***** Necessary DC characterization

• ΔN noise for $|V_{GS}-V_T| < 0.2V$

- *** LFN can be referred to gate terminal**
- Trade-off between noise performance and GeC concentration

Noise scaling

- $(S_{I_D})_{avg} \propto I_D^2/(f \times Area)$
- ***** Log-normal distribution \Rightarrow averaging and deviation in dB

Several factors contribute to LFN at increased gate biasing |V_{GS}-V_T|>0.4V

